

Amendments to the Claims

The claims have been amended as follows. Underlines indicate insertions and strikeouts indicate deletions.

Claims 1-84 (Cancelled)

85. (Currently amended) A sputtering target comprising Zr and one or more elements selected from the group consisting of ~~Al, B,~~ Ba, Be, Ca, Ce, Co, Cs, Dy, Er, Fe, Gd, ~~Hf,~~ Ho, La, Mg, Mn, Mo, ~~Nb,~~ Nd, ~~Ni,~~ Pr, Sc, Sm, Sr, ~~Ta,~~ V, W, ~~Y,~~ and Yb; the Zr being the majority element of the target.

B2 86. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 70%.

87. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 90%.

88. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 94%.

89. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 97%.

90. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is less than 98%.

91. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is in a range of from 0.001% to 50% of the ~~ingot~~ target.

B²
Cont'd
92. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is in a range of 0.001% to 10% of the ~~ingot~~ target.

93. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 0.01% of the ~~ingot~~ target.

94. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 0.1% of the ~~ingot~~ target.

95. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 1% of the ~~ingot~~ target.

96. (Currently amended) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 2% of the ~~ingot~~ target.

97. (Currently amended) The sputtering target of claim 85 ~~consisting of Zr~~ further comprising one or more elements selected from the group consisting of Al, B, Hf, Nb, Ni, Ta, Y and Ti.

98. (Currently amended) A sputtering target consisting essentially of a material having a purity of at least 99.95%, by weight, the material comprising Zr and Ti; the Zr being the majority element of the target and being present to a concentration within the target of at least 55%.

B²
Cont'd
99. (Original) The sputtering target of claim 98 wherein the Zr concentration within the target is at least 70%.

100. (Original) The sputtering target of claim 98 wherein the Zr concentration within the target is at least 90%.

101. (Original) The sputtering target of claim 98 wherein the Zr concentration within the target is at least 94%.

102. (Original) The sputtering target of claim 98 wherein the Zr concentration within the target is at least 97%.

103. (Original) The sputtering target of claim 98 wherein the Zr concentration within the target is less than 98%.

104. (Currently amended) A sputtering target comprising Ti and greater than 0.2% B, by weight; the Ti being the majority element of the target.

105. (Original) The sputtering target of claim 104 wherein the Ti concentration within the target is at least 70%.

106. (Original) The sputtering target of claim 104 wherein the Ti concentration within the target is at least 90%.

107. (Original) The sputtering target of claim 104 wherein the Ti concentration within the target is at least 94%.

108. (Original) The sputtering target of claim 104 wherein the Ti concentration within the target is at least 97%.

Claims 109-117 (Cancelled).

118. (Original) The sputtering target of claim 104 consisting of Ti and B.
